

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/065,568	10/31/2002	Kuo-Ming Chen	NAUP0482USA	7641
27765	7590 07/23/200	4	EXAMINER	
•	ORTH AMERICA IN	LEBENTRITT, MICHAEL		
P.O. BOX 506 MERRIFIELD, VA 22116			ART UNIT	PAPER NUMBER
	·		2824	-
			DATE MAILED: 07/23/200	4

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/065,568	CHEN ET AL.				
Office Action Summary	Examiner	Art Unit				
	Michael S. Lebentritt	2824				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period of Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on amdt	filed 5/24/04.					
<u> </u>	action is non-final.					
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) ☐ Claim(s) 1-4 and 6-9 is/are pending in the apple 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-4 and 6-9 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/o are subject to restriction and/o are subjected to by the Examine 10) ☐ The specification is objected to by the Examine 10) ☐ The drawing(s) filed on 31 October 2002 is/are: Applicant may not request that any objection to the	wn from consideration. r election requirement. r. : a) □ accepted or b) □ objected					
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document: 2. Certified copies of the priority document: 3. Copies of the certified copies of the priority document: application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:					

Application/Control Number: 10/065,568

Art Unit: 2824

DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Beddingfield, US Patent 5,977,632 in view of Dass et al, US Patent 6,162,652 and further in view of Applicant's Admitted Prior Art (AAPA).

Beddingfield discloses providing a semiconductor wafer(10), which comprises a substrate (10), an integrated circuit (not shown), and at Least one bump pad (12)formed on the substrate and electrically connected with the integrated circuit', forming a first dielectric Layer (16) on a surface of the bump pad; performing an etching process to form a contact hole in the first dielectric layer (figure 1) and to expose a portion of the bump pad (12); forming a second dielectric layer (18) on a surface of the semiconductor wafer outside of the contact hole, performing an under bump metallurgy (UBM) process so as to form a metal layer (24) on a surface of the contact hole; forming a solder bump (26) on the metal layer corresponding to the contact hole; and performing a connection process to complete connection of the semiconductor wafer

Art Unit: 2824

and a packaging board (figure 7). Please see figures 1-7 and discussion on column 2, line 35 to column 4, and line 35. Also in regards to claim 6 wherein the second dielectric layer is composed of insulating materials. such as benocyclobutene (BCB), polyimide (PI), and BCB+PI (column 3, lines 5 to 15.

Beddingfield is applied supra but lacks the anticipation of wherein the circuit probing and an laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump. Dass discloses circuit probing and an laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump. See figures 17 and discussion on column 7, line 45 to column 8, line 30. In view of this disclosure it would have been obvious to one of ordinary skill in the art at the time of invention to circuit probing and a laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump as taught by Dass et al, because by testing after bumping and before laser repair the throughput is increased.

In regards to claims 2-4, Beddingfield is applied supra but lacks the anticipation wherein the semiconductor wafer further comprises'. a plurality of fuses electrically connected with the integrated circuit; at Least one alignment key; and a silicon oxide layer formed on a surface of the fuses and the alignment key. AAPA discloses a semiconductor wafer 1 0 comprises a substrate 1 2, which has an integrated circuit region (not shown) comprising an embedded memory array formed on its surface. The

surface of the substrate 1 2 further comprises a bump pad 1 4, a plurality of fuses 1 6, and an alignment key 1 8. The bump pad 1 4 is electrically connected with the integrated circuit region. Therefore, after completing a subsequent packaging process, the integrated circuit is able to electrically connect to an external circuit through the bump pad 1 4. In view of this disclosure it would of been obvious to one of ordinary skill in the art at the time of invention to form a plurality of fuses electrically connected with the integrated circuit; at Least one alignment key; and a silicon oxide layer formed on a surface of the fuses and the alignment key as taught by AAPA in view of the primary reference of Beddingfield, because the alignment key provides a means for visual inspection and the fuse provide electrical connection for probe testing.

Claims 7-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Loo et al, US Patent 6,118,180 in view of Dass et al, US Patent 6,162,652 and further in view of Applicant's Admitted Prior Art (AAPA)

Loo discloses providing a semiconductor wafer (400), which comprises a substrate, an integrated circuit, and at Least one bump pad (402) formed on the substrate and electrically connected with the integrated circuit-, forming a dielectric layer (406) on a surface of the bump pad; performing an etching process to form a contact hole in the dielectric layer (figure 6) and ' to expose a portion of the bump pad; performing an under bump metallurgy (UBM) process so as to form a metal layer (408) on a surface of the contact hole; forming a solder bump (412) on the metal layer corresponding to the contact hole; and performing a connection process to complete

Art Unit: 2824

connection of the semiconductor wafer and a packaging board. See figures 3-6 and discussion on column 5, line 30 to column 8, line 15.

Loo is applied supra but lacks the anticipation of wherein the circuit probing and an laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump. Dass discloses circuit probing and an laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump. See figures 17 and discussion on column 7, line 45 to column 8, line 30. In view of this disclosure it would have been obvious to one of ordinary skill in the art at the time of invention to circuit probing and a laser repair process are performed after the formation of the solder bump, and a probing tip is used to perform the circuit probing process by electrically connecting with the solder bump as taught by Dass et al, because by testing after bumping and before laser repair the throughput is increased.

In regards to claims 8 and 9, Loo is applied supra but lacks the anticipation wherein the semiconductor wafer further comprises'. a plurality of fuses electrically connected with the integrated circuit; at Least one alignment key; and a silicon oxide layer formed on a surface of the fuses and the alignment key. AAPA discloses a semiconductor wafer 1 0 comprises a substrate 1 2, which has an integrated circuit region (not shown) comprising an embedded memory array formed on its surface. The surface of the substrate 1 2 further comprises a bump pad 1 4, a plurality of fuses 1 6, and an alignment key 1 8. The bump pad 1 4 is electrically connected with the integrated

Application/Control Number: 10/065,568 Page 6

Art Unit: 2824

circuit region. Therefore, after completing a subsequent packaging process, the integrated circuit is able to electrically connect to an external circuit through the bump pad 1.4. In view of this disclosure it would of been obvious to one of ordinary skill in the art at the time of invention to form a plurality of fuses electrically connected with the integrated circuit; at Least one alignment key; and a silicon oxide layer formed on a surface of the fuses and the alignment key as taught by AAPA in view of the primary reference of Loo, because the alignment key provides a means for visual inspection and the fuse provide electrical connection for probe testing.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael S. Lebentritt whose telephone number is 571-272-1873. The examiner can normally be reached on 5/4/9.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Richard Elms can be reached on 571-272-1869. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-3431.

Michael S. Lebentritt Primary Examiner Art Unit 2824